

# **Special Topics on Basic EECS I**

## **Design Technology Co-Optimization**

### **Lecture 21**

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# L21

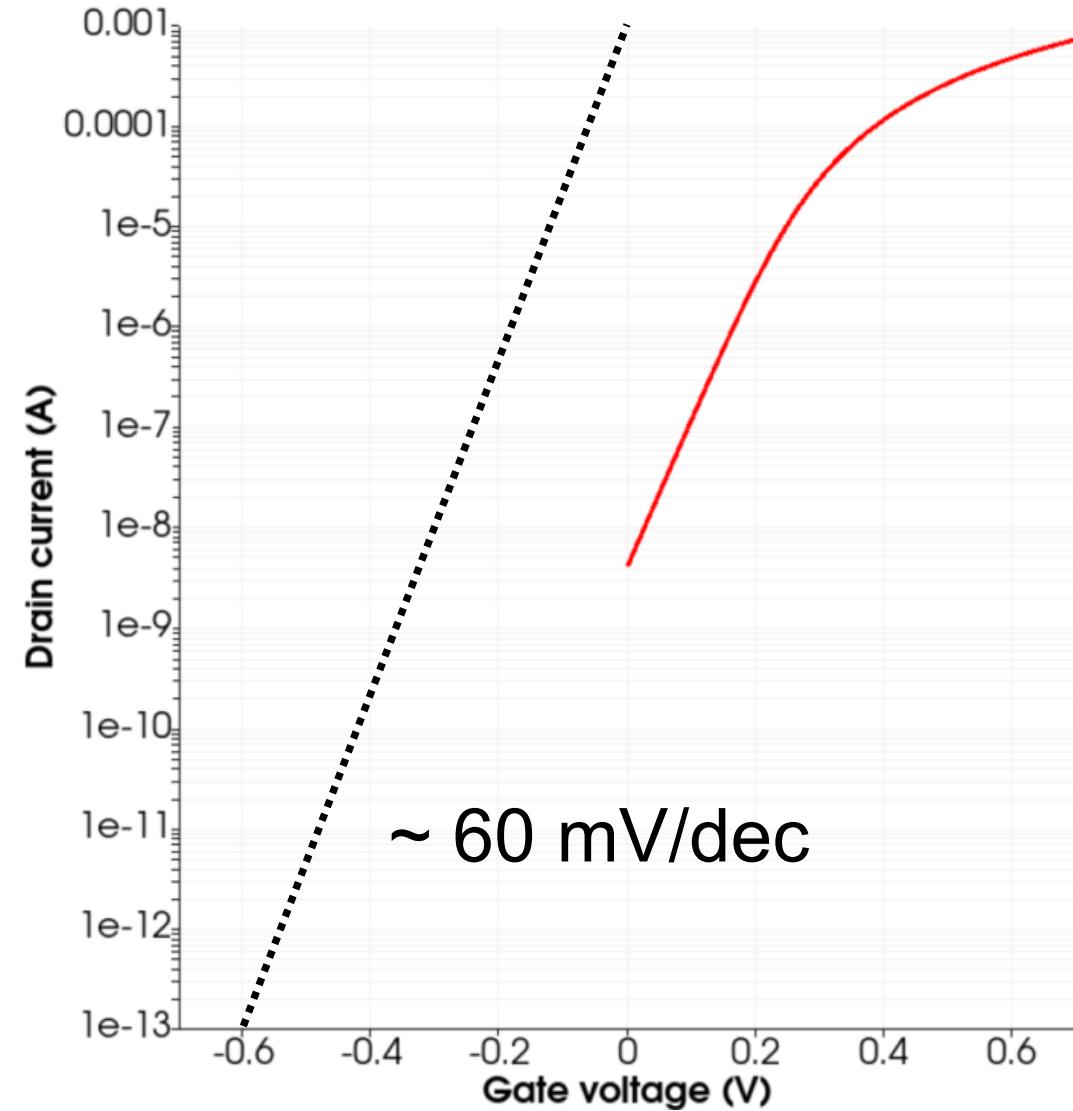
# Reduction of vertex counts

- Keep only a part within the CPP.
  - The very initial region is kept.
  - Now, about 100k vertex points



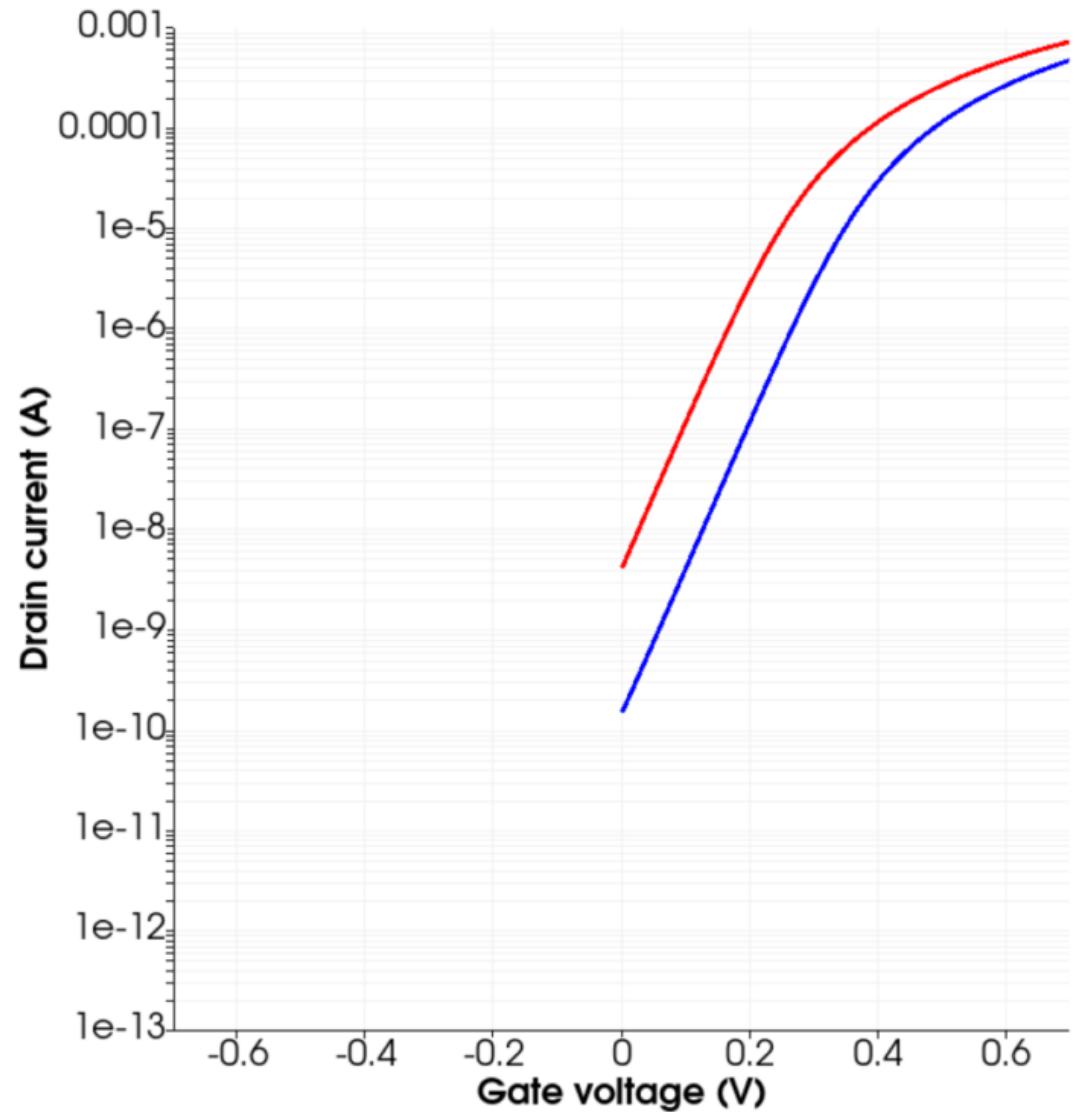
# Input curve without any physical model

- Using the previous input file, we can simulate the FinFET.
  - Gate workfunction of 4.4 eV
  - It takes time. (4k sec in my environment)
  - The OFF current, 4.1 nA
  - The ON current, 723.9  $\mu$ A  
(← Again, highly overestimated)
  - Start your simulation now.



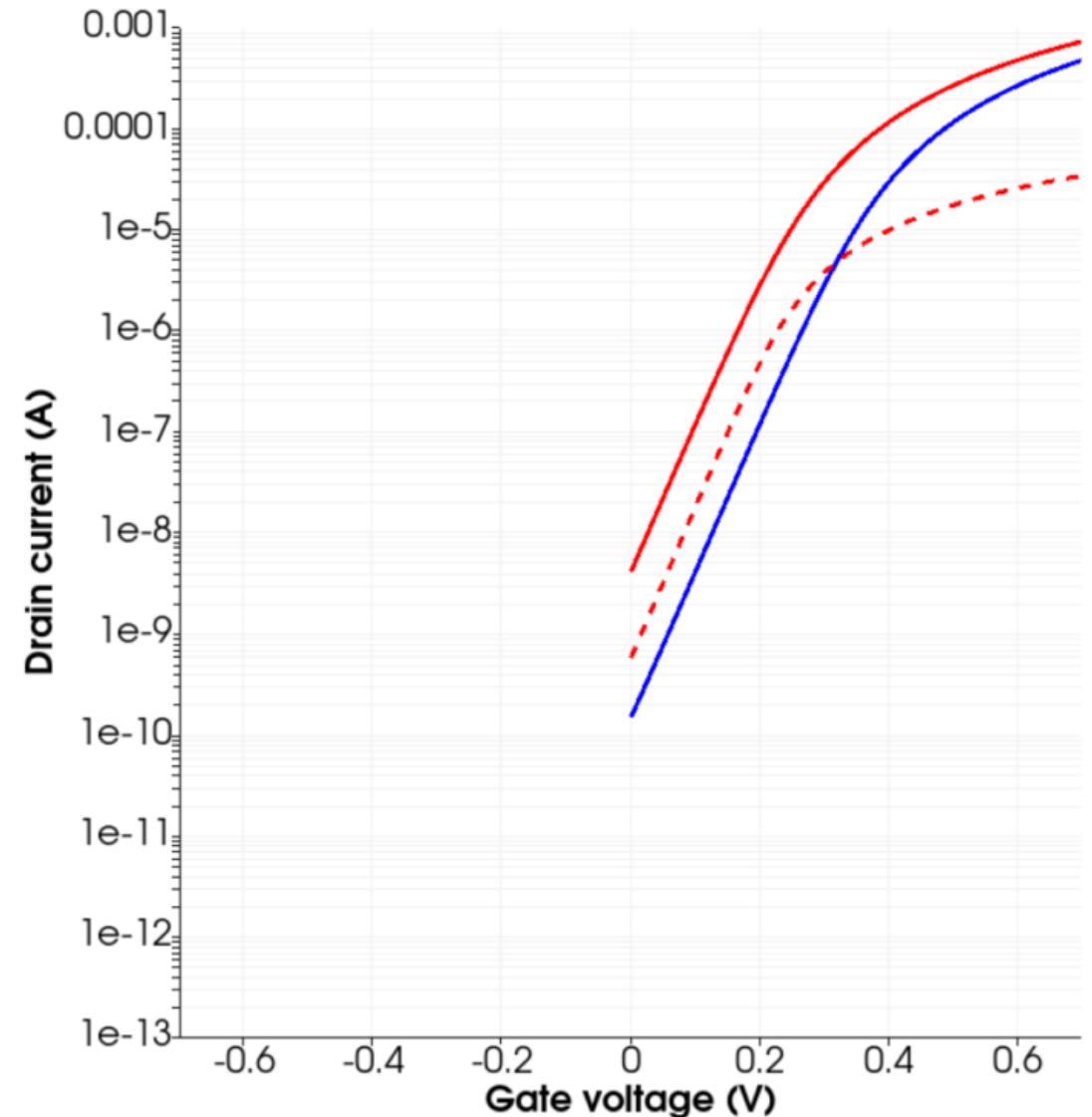
# Workfunction of 4.5 eV

- As expected, the IV curves shifts with the workfunction.
  - The OFF current, 0.14 nA
  - The ON current, 472.1  $\mu$ A



# Mobility model and SRH model

- Significant reduction of drain current
  - Gate workfunction of 4.4 eV
  - The OFF current, 0.57 nA (It was 4.1 nA.)
  - The ON current, 33.9  $\mu$ A (It was 723.9  $\mu$ A.)



# Homework#21

- Due: 08:00 on Dec. 1
- Submit a report through the GIST LMS system.
  - The ASAP7 PDK results are shown below. Calculate your  $I_{dsat}$  and  $I_{off}$  with your own setting. Then, compare your results with the table.

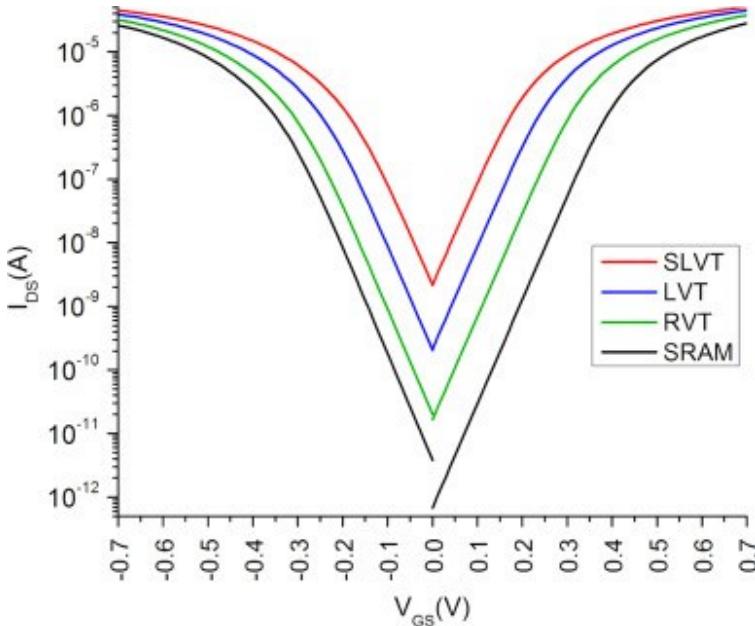


Table 3. NMOS typical corner parameters (per fin) at 25 °C.

Parameter	SRAM	RVT	LVT	SLVT
$I_{dsat}$ ( $\mu$ A)	28.57	37.85	45.19	50.79
$I_{eff}$ ( $\mu$ A)	13.07	18.13	23.56	28.67
$I_{off}$ (nA)	0.001	0.019	0.242	2.444
$V_{tsat}$ (V)	0.25	0.17	0.10	0.04
$V_{tdin}$ (V)	0.27	0.19	0.12	0.06
SS (mV/decade)	62.44	63.03	62.90	63.33
DIBL (mV/V)	19.23	21.31	22.32	22.55

# Thank you!